

CPC**COOPERATIVE PATENT CLASSIFICATION****G02F**

DEVICES OR ARRANGEMENTS, THE OPTICAL OPERATION OF WHICH IS MODIFIED BY CHANGING THE OPTICAL PROPERTIES OF THE MEDIUM OF THE DEVICES OR ARRANGEMENTS FOR THE CONTROL OF THE INTENSITY, COLOUR, PHASE, POLARISATION OR DIRECTION OF LIGHT, e.g. SWITCHING, GATING, MODULATING OR DEMODULATING; TECHNIQUES OR PROCEDURES FOR THE OPERATION THEREOF; FREQUENCY-CHANGING; NON-LINEAR OPTICS; OPTICAL LOGIC ELEMENTS; OPTICAL ANALOGUE/DIGITAL CONVERTERS ([optical transfer means between sensing member and indicating or recording part in connection with measuring G01D 5/26](#) ; devices in which mathematical operations are carried out with optical elements [G06E 3/00](#) , { [G06E 3/001](#) } ; electrical signal transmission systems using optical means to convert the input signal [G08C 19/36](#) ; information-recording by electric or magnetic means and reproducing by sensing optical properties [G11B 11/00](#) ; static stores using optical elements [G11C 13/04](#) ; transmission systems employing electromagnetic waves other than radio waves, e.g. light, infra-red radiation, [H04B 10/00](#) ; optical multiplex systems [H04J 14/00](#) ; pictorial communication, e.g. television [H04N](#))

WARNING

The following IPC group is not used in the CPC scheme.
 Subject matter covered by these groups is classified in the following CPC groups:
 - [G02F 1/13357](#) covered by [G02F 1/1336](#) and subgroups

G02F 1/00

Devices or arrangements for the control of the intensity, colour, phase, polarisation or direction of light arriving from an independent light source, e.g. switching, gating, or modulating; Non-linear optics ([thermometers using change of colour or translucency G01K 11/12](#) ; using changes in fluorescence [G01K 11/32](#) ; light guide devices [G02B 6/00](#) ; optical devices or arrangements using movable or deformable elements for controlling light independent of the light source [G02B 26/00](#) ; control of light in general [G05D 25/00](#) ; visible signalling systems [G08B 5/00](#) ; indicating arrangements for variable information by selection or combination of individual elements [G09F 9/00](#) ; control arrangements or circuits for visual indicators other than cathode-ray tubes [G09G 3/00](#) ; control of light sources [H01S 3/10](#) , [H05B 33/08](#) , [H05B 35/00](#) to [H05B 43/00](#) ; { [photochromic filters G02B 5/23](#) ; [optical logic elements G02F 3/00](#) })

NOTE

This group covers only :

- devices or arrangements, e.g. cells, the optical operation of which is modified by changing the optical properties of the medium of the devices or arrangements by the influence or control of physical parameters, e.g. electric fields, electric current, magnetic fields, sound or mechanical vibrations, stress or thermal effects;
- devices or arrangements in which the electric or magnetic field component of the light beams influences the optical properties of the medium, i.e. non-linear optics;
- control of light by electromagnetic waves, e.g. radio waves,

or by electrons or other elementary particles.

G02F 1/0009 . { Materials therefor }

NOTE

G02F 1/0009 and subgroups contain mostly non-patent literature

- G02F 1/0018 . . { Electro-optical materials }
- G02F 1/0027 . . . { with ferro-electric properties (domain inversion in ferro-electric materials G02F 1/3558 ; ferro-electric materials in general H01G 7/02) }
- G02F 1/0036 . . { Magneto-optical materials (magnetic materials in general H01F) }
- G02F 1/0045 . . { Liquid crystals as far as the physical properties are concerned (chemical composition and properties of liquid crystals C09K 19/00) }
- G02F 1/0054 . . { Structure, phase transitions, NMR, ESR, Moessbauer spectra }
- G02F 1/0063 . . { Optical properties e.g. absorption, reflection, non-linear effects, birefringence (non linear optics in general G02F 1/35) }
- G02F 1/0072 . . { Mechanical, acoustic, electro-elastic, magneto-elastic properties }
- G02F 1/0081 . . { Electric or magnetic properties }
- G02F 1/009 . . { Thermal properties (thermometers using change of colour or translucency G01K 11/12 ; radiation pyrometry G01J 5/00) }

- G02F 1/01 . for the control of the intensity, phase, polarisation or colour (G02F 1/29 , G02F 1/35 take precedence; polarising elements per se G02B 5/30 ; static storage per se G11C; image tube screens acting as light valves by shutter operation H01J 29/12 ; such screens acting by discoloration H01J 29/14 ; { projection arrangements for television image reproduction, e.g. using eidophor H04N 5/74 ; recording by light G11B 7/00 to G11B 11/00 })
- G02F 1/0102 . . { Constructional details (G02F 1/1306 , G02F 1/133 take precedence) }
- G02F 1/0105 . . . { Illumination devices (for liquid crystal cells G02F 1/13357 ; for display devices for electronic time pieces G04G 9/0041) }
- G02F 1/0107 . . . { Gaskets, spacers, sealing of the cell; Filling and closing of the cell (for liquid crystal cells G02F 1/1339 , G02F 1/1341 ; for electrochromic or electrolytic cells G02F 1/161) }
- G02F 1/011 . . { in optical waveguides (G02F 1/0134 , G02F 1/01708 , G02F 1/025 , G02F 1/035 , G02F 1/0508 , G02F 1/0553 , G02F 1/065 , G02F 1/073 , G02F 1/095 , G02F 1/125 , G02F 1/1326 , G02F 1/225 take precedence; optical waveguides in general G02B 6/00) }
- G02F 2001/0113 . . . made of glass, e.g. silica-based optical waveguides
- G02F 1/0115 . . . { in optical fibres }
- G02F 1/0118 { by controlling the evanescent coupling of light from a fibre into an active, e.g. electro-optic, overlay }
- G02F 1/0121 . . { Operation of the device; Circuit arrangements not otherwise provided for (G02F 1/0327 , G02F 1/0516 , G02F 1/076 , G02F 1/092 , G02F 1/113 , G02F 1/13306 , G02F 1/163 take precedence) }
- G02F 1/0123 . . . { Circuits for the control or stabilisation of the bias voltage, e.g. automatic bias control (ABC) feedback loops }

- G02F 1/0126 .. { by another light beam, i.e. opto-optical modulation ([G02F 1/01716](#) , [G02F 1/0338](#) , [G02F 1/0533](#) , [G02F 1/0541](#) , [G02F 1/0558](#) , [G02F 1/135](#) , [G02F 1/293](#) take precedence) }
- G02F 1/0128 .. { based on electro-mechanical, magneto-mechanical, elasto-optic effects }
- G02F 1/0131 ... { based on elasto-optic, i.e. photoelastic effect, e.g. mechanically induced birefringence ([acousto-optic devices G02F 1/11](#)) }
- G02F 1/0134 { in optical waveguides }
- G02F 1/0136 .. { for the control of polarisation, e.g. state of polarisation (SOP) control, polarisation scrambling, TE-TM mode conversion or separation ([G02F 1/0353](#) takes precedence) }
- G02F 2001/0139 ... Polarisation scrambling; Depolarisers
- G02F 2001/0142 ... TE-TM mode conversion
- G02F 2001/0144 ... TE-TM mode separation
- G02F 1/0147 .. { based on thermo-optic effects ([G02F 1/132](#) takes precedence; tenebrescent compositions [C09K 9/00](#) ; radiation pyrometry [G01J 5/00](#) ; thermometers using change of colour or translucency [G01K 11/12](#)) }
- G02F 1/015 .. based on semiconductor elements with at least one potential jump barrier, e.g. PN, PIN junction ([G02F 1/03](#) takes precedence)
- G02F 2001/0151 ... modulating the refractive index
- G02F 2001/0152 by free carrier effects (Plasma)
- G02F 2001/0153 by electro-refraction ([Kramers-Kronig relation](#))
- G02F 2001/0154 by electro-optic effects ([LEO=Pockels](#), [QEO=Kerr](#))
- G02F 2001/0155 ... modulating the optical absorption
- G02F 2001/0156 by free carrier absorption
- G02F 2001/0157 by electro-absorption effects ([FK](#), [Stark](#), [QCSE](#))
- G02F 2001/0158 with blue-shift of the absorption band
- G02F 2001/0159 with red-shift of the absorption band
- G02F 1/017 ... Structures with periodic or quasi periodic potential variation, e.g. superlattices, quantum wells
- G02F 1/01708 { in an optical waveguide structure }
- G02F 1/01716 { [Optically controlled superlattice or quantum well devices](#) }
- G02F 1/01725 { [with a non-rectangular quantum well structure, e.g. coupled, graded, stepped quantum wells](#) }
- G02F 2001/01733 Coupled or double quantum wells
- G02F 2001/01741 Asymmetrically coupled or double quantum wells
- G02F 2001/0175 with a spatially varied well profile, e.g. graded, stepped quantum wells
- G02F 2001/01758 with an asymmetric well profile, e.g. asymmetrically stepped quantum wells
- G02F 2001/01766 Strained superlattice or quantum well devices
- G02F 2001/01775 involving an intersubband transition in one well, e.g. $e_1 \rightarrow e_2$
- G02F 2001/01783 Quantum wire
- G02F 2001/01791 Quantum box or dot
- G02F 1/025 ... in an optical waveguide structure ([G02F 1/017](#) , { [G02F 1/2257](#) } take precedence)
- G02F 1/03 .. based on ceramics or electro-optical crystals, e.g. exhibiting Pockels effect or Kerr effect ([G02F 1/061](#) takes precedence)

G02F 1/0305	...	{ Constructional arrangements (G02F 1/0327 to G02F 1/05 take precedence) }
G02F 1/0311	{ Structural association of optical elements, e.g. lenses, polarizers, phase plates, with the crystal }
G02F 1/0316	{ Electrodes }
G02F 1/0322	{ Arrangements comprising two or more independently controlled crystals }
G02F 1/0327	...	{ Operation of the cell; Circuit arrangements (G02F 1/05 takes precedence) }
G02F 1/0333	...	{ addressed by a beam of charged particles e.g. directed to an adjacent layer exhibiting secondary emission or bombardment-induced conductivity effect (G02F 1/05 takes precedence; electrography, electrophotography G03G ; screens for cathode ray tubes acting as light valves H01J 29/12) }
G02F 1/0338	...	{ structurally associated with a photoconductive layer or having photo-refractive properties (G02F 1/05 takes precedence) }
G02F 1/0344	...	{ controlled by a high-frequency electromagnetic wave component in an electric waveguide (G02F 1/0356 , G02F 1/05 , G02F 1/2255 , G02F 1/3134 take precedence) }
G02F 1/035	...	in an optical waveguide structure
G02F 1/0353	{ involving an electro-optic TE-TM mode conversion }
G02F 1/0356	{ controlled by a high-frequency electromagnetic wave component in an electric waveguide structure }
G02F 1/05	...	with ferro-electric properties (G02F 1/035 , G02F 1/055 take precedence; { domain inversion in ferro-electric materials G02F 1/3558 ; ferro-electric digital stores G11C 11/22 })
G02F 1/0508	{ specially adapted for gating or modulating in optical waveguides }
G02F 1/0516	{ Operation of the cell; Circuit arrangements }
G02F 1/0525	{ addressed by a beam of charged particles, e.g. directed to an adjacent layer exhibiting secondary emission or bombardment-induced conductivity effect (electrography, electrophotography G03G ; screens for cathode-ray tubes acting as light valves H01J 29/12) }
G02F 1/0533	{ structurally associated with a photo-conductive layer }
G02F 1/0541	{ using photo-refractive effects (holography G03H ; electro-optical digital static stores using an interference pattern G11C 13/044) }
G02F 1/055	...	the active material being a ceramic (G02F 1/035 takes precedence)
G02F 1/0551	{ Constructional details }
G02F 1/0553	{ specially adapted for gating or modulating in optical waveguides }
G02F 1/0555	{ Operation of the cell; Circuit arrangements }
G02F 1/0556	{ specially adapted for a particular application }
G02F 1/0558	{ structurally associated with a photoconductive layer or exhibiting photo-refractive properties }
G02F 1/061	..	based on electro-optical organic material (G02F 1/07 , { G02F 1/13 } take precedence)
G02F 1/065	...	in an optical waveguide structure
G02F 1/07	..	based on electro-optical liquids exhibiting Kerr effect
G02F 1/073	...	{ specially adapted for gating or modulating in optical waveguides }
G02F 1/076	...	{ Operation of the cell; Circuit arrangements }
G02F 1/09	..	based on magneto-optical elements, e.g. exhibiting Faraday effect
G02F 1/091	...	{ based on magneto-absorption or magneto-reflection }

G02F 1/092	...	{ Operation of the cell; Circuit arrangements }
G02F 1/093	...	{ used as non-reciprocal devices, e.g. optical isolators, circulators (G02F 1/0955 takes precedence) }
G02F 2001/094	...	Based on magnetophoretic effect
G02F 1/095	...	in an optical waveguide structure
G02F 1/0955	{ used as non-reciprocal devices, e.g. optical isolators, circulators }
G02F 1/11	..	based on acousto-optical elements, e.g. using variable diffraction by sound or like mechanical waves ({ elasto-optic effect without wave propagation G02F 1/0131 ; } acousto-optical deflection G02F 1/33) }
G02F 1/113	...	{ Circuit or control arrangements }
G02F 1/116	...	{ using an optically anisotropic medium, wherein the incident and the diffracted light waves have different polarizations, e.g. acousto-optic tunable filter (AOTF) (G02F 1/125 takes precedence) }
G02F 1/125	...	in an optical waveguide structure
G02F 1/13	..	based on liquid crystals, e.g. single liquid crystal display cells (liquid crystal materials C09K 19/00)
G02F 1/1303	...	{ Apparatus specially adapted to the manufacture of LCDs }
G02F 1/1306	...	{ Details (not used, see sub-groups) }
G02F 1/1309	{ Repairing; Testing (testing of optical apparatus G01M 11/00 ; electronic testing of displays or display drivers, e.g. of LCDs, G09G 3/006) }
G02F 1/1313	...	{ specially adapted for a particular application }
G02F 2001/1316	...	Cleaning methods or materials for cleaning part of liquid crystal cell components during the manufacturing process
G02F 1/132	...	{ Thermal activation of liquid crystals exhibiting a thermo-optic effect (thermometers using change of colour or translucency of liquid crystals G01K 11/165 ; thermally addressed liquid crystal elements in a matrix G09G 3/3603) }
G02F 1/1323	...	{ Arrangements for providing a switchable viewing angle }
G02F 1/1326	...	{ Liquid crystal optical waveguides or liquid crystal cells specially adapted for gating or modulating between optical waveguides }
G02F 1/133	...	Constructional arrangements; Operation of liquid crystal cells; Circuit arrangements (arrangements or circuits for control of liquid crystal elements in a { segment display or a }matrix, not structurally associated with these elements, { respectively G09G 3/18 and } G09G 3/36) }
G02F 1/13306	{ Circuit arrangements or driving methods for the control of single liquid crystal cells (G02F 1/132 , G02F 1/133382 take precedence) }
G02F 2001/13312	Circuits comprising a photodetector not for feedback
G02F 1/13318	{ Circuits comprising a photodetector }
G02F 2001/13324	Circuits comprising a solar cell
G02F 1/1333	Constructional arrangements; { Manufacturing methods } (G02F 1/135 , G02F 1/136 take precedence) }
G02F 2001/133302	rigid substrate, e.g. inorganic
G02F 1/133305	{ Flexible substrates, e.g. plastics, organic film }
G02F 1/133308	{ LCD panel immediate support structure, e.g. front and back frame or bezel }
G02F 2001/133311	Environmental protection, e.g. dust, humidity
G02F 2001/133314	Back frame
G02F 2001/133317	Intermediate frame, e.g. between backlight housing and front frame

G02F 2001/13332	Front frame
G02F 2001/133322	Mechanical guiding and alignment of LCD panel support components
G02F 2001/133325	Method of assembling (G02F 2201/465 takes precedence)
G02F 2001/133328	Segmented frame
G02F 2001/133331	Cover glass
G02F 2001/133334	Electromagnetic shield
G02F 2001/133337	Ion-diffusion preventing or absorbing layer
G02F 1/13334	{ Plasma addressed liquid crystal cells [PALC] (plasma panels H01J 17/49) }
G02F 2001/133342	for double side displays
G02F 1/133345	{ Insulating layers (G02F 1/1335 , G02F 1/1337 , G02F 1/135 , G02F 1/136 take precedence) }
G02F 1/133348	{ Charged-particles, e.g. electron-beam, addressed liquid crystals cells (screen for cathode ray tubes acting as light valves H01J 29/12 ; electrography, electrophotography G03G) }
G02F 1/133351	{ Manufacturing of individual cells out of a plurality of cells, e.g. by dicing }
G02F 2001/133354	Arrangements for aligning or assembling the substrates
G02F 2001/133357	Planarisation layer
G02F 1/13336	{ Combining plural substrates to produce large-area displays, e.g. tiled displays }
G02F 1/133362	{ Optically addressed liquid crystal cells (G02F 1/135 takes precedence) }
G02F 1/133365	{ Cells in which the active layer comprises a liquid crystalline polymer (liquid crystalline polymers in general C09K 19/38) }
G02F 2001/133368	cell having two substrates with different characteristic, e.g. thickness or material
G02F 1/133371	{ Cells with varying thickness of the liquid crystal layer }
G02F 2001/133374	for displaying permanent signs or marks
G02F 1/133377	{ Cells with plural compartments or having plurality of liquid crystal micro-cells partitioned by walls, e.g. one micro-cell per pixel }
G02F 1/13338	{ Input devices, e.g. touch-panels (specially adapted as input devices to computers G06F 3/033 ; touch-panels per se G06K 11/06 , keyboard switches per se H01H 13/70) }
G02F 1/133382	{ Heating or cooling of liquid crystal cells other than for activation, e.g. circuits or arrangements for temperature control, stabilisation or uniform distribution over the cell }
G02F 1/133385	{ with cooling means, e.g. fans }
G02F 2001/133388	Constructional difference between the display region and the peripheral region
G02F 2001/133391	Constructional arrangement for sub-divided displays
G02F 2001/133394	Piezoelectric element associated with the cell
G02F 2001/133397	for suppressing after-image or image-sticking
G02F 1/1334	based on polymer dispersed liquid crystals, e.g. microencapsulated liquid crystals {(compositions C09K 19/544) }
G02F 1/13342	{ Holographic polymer dispersed liquid crystals }
G02F 2001/13345	Network or three-dimensional gel
G02F 2001/13347	Reverse mode, i.e. clear in the off-state and scattering in the on-state

G02F 1/1335	Structural association of optical devices, e.g. polarisers, reflectors or illuminating devices, with the cell
G02F 1/133502	{ Antiglare, refractive index matching layers }
G02F 1/133504	{ Diffusing, scattering, diffracting elements (associated to illuminating devices G02F 1/13357) }
G02F 2001/133507	Luminance enhancement films
G02F 1/133509	{ Filters, e.g. light shielding masks (optical filters G02B 5/20) }
G02F 1/133512	{ Light shielding layers, e.g. black matrix (G02F 1/136209 takes precedence) }
G02F 1/133514	{ Colour filters (luminescent elements G02F 1/13357L) }
G02F 1/133516	{ Methods of making thereof, e.g. printing, electro-deposition, photolithography (photomechanical production of textured or patterned surfaces G03F) }
G02F 2001/133519	overcoating
G02F 2001/133521	Interference filters
G02F 1/133524	{ Light-guides, e.g. fibre-optic bundles, louvered or jalousie light-guides }
G02F 1/133526	{ Lenses, e.g. micro-lenses, Fresnel lenses (lenses in general G02B 3/00) }
G02F 1/133528	{ Polarisers (polarisers per se G02B 5/30) }
G02F 2001/133531	Special arrangement of polariser or analyser axes
G02F 1/133533	{ Colour selective polarisers (G02F 1/1347 takes precedence) }
G02F 1/133536	{ Reflective polarizers (G02F 1/13357P takes precedence) }
G02F 2001/133538	with a spatial distribution of the polarisation direction
G02F 2001/133541	Circular polarisers
G02F 2001/133543	Cholesteric polarisers
G02F 2001/133545	Dielectric stack polarisers
G02F 2001/133548	Wire-grid polarisers
G02F 2001/13355	Polarising beam splitters [PBS]
G02F 1/133553	{ Reflecting elements (associated to illuminating devices G02F 1/13357) }
G02F 1/133555	{ Transflectors }
G02F 2001/133557	Half-mirror
G02F 2001/13356	Particular location of the optical element
G02F 2001/133562	on the viewer side
G02F 2001/133565	inside the LC element, i.e. between the cell substrates
G02F 2001/133567	on the back side
G02F 1/1336	{ Illuminating devices (in general F21V ; associated with display devices for electronic watches G04G 9/0041) }

WARNING

Groups [G02F 1/1336](#) - [G02F 1/133621](#) dos not correspond to former or current IPC groups. Concordance CPC : IPC for these groups is as follows: - [G02F 1/1336](#) - [G02F 1/133621](#) : [G02F 1/13357](#)

G02F 2001/133601	for spatial active dimming
G02F 1/133602	{ Direct backlight }
G02F 1/133603	{ with LEDs }
G02F 1/133604	{ with lamps }
G02F 1/133605	{ including specially adapted reflectors }
G02F 1/133606	{ including a specially adapted diffusing, scattering or light controlling members }
G02F 2001/133607	the light controlling member including light directing or refracting elements, e.g. prisms or lenses
G02F 1/133608	{ including particular frames or supporting means }
G02F 1/133609	{ including means for improving the color mixing, e.g. white }
G02F 1/133611	{ including means for improving the brightness uniformity }
G02F 2001/133612	Electrical details
G02F 2001/133613	including a particular sequence of light sources
G02F 2001/133614	the light is generated by photoluminescence, e.g. a phosphor is illuminated by UV or blue light
G02F 1/133615	{ Edge-illuminating devices, i.e. illuminating from the side (G02B 6/0001 takes precedence) }
G02F 2001/133616	Front illuminating devices
G02F 1/133617	{ Illumination with ultra-violet light; Luminescent elements or materials associated to the cell }
G02F 2001/133618	for ambient light
G02F 1/13362	{ providing polarised light, e.g. by converting a polarisation component into another one (optical systems for polarising G02B 27/28) }
G02F 1/133621	{ providing coloured light (G02F 1/133617 , G02F 1/133533 take precedence) }
G02F 2001/133622	colour sequential illumination
G02F 2001/133623	Inclined coloured light beams
G02F 2001/133624	having a particular spectral emission
G02F 2001/133625	Electron stream lamps
G02F 2001/133626	providing two modes of illumination, e.g. day-night
G02F 2001/133627	Projection-direct viewing
G02F 2001/133628	with cooling means
G02F 1/13363	Birefringent elements, e.g. for optical compensation
G02F 2001/133631	with a spatial distribution of the retardation value
G02F 1/133632	{ with refractive index ellipsoid inclined relative to the LC-layer surface }
G02F 2001/133633	using mesogenic materials
G02F 1/133634	{ the refractive index Nz perpendicular to the element surface being different from in-plane refractive indices Nx and Ny, e.g. biaxial or with normal optical axis }
G02F 2001/133635	Multifunctional compensators
G02F 1/133636	{ with twisted orientation, e.g. comprising helically oriented LC-molecules or a plurality of twisted birefringent sublayers }
G02F 2001/133637	characterized by the wavelength dispersion

G02F 2001/133638	Waveplates, i.e. plates with a retardation value of λ/n
G02F 1/1337	Surface-induced orientation of the liquid crystal molecules, e.g. by alignment layers
G02F 1/133703	{ by introducing organic surfactant additives into the liquid crystal material (C09K 19/56 takes precedence) }
G02F 1/133707	{ Structures for producing distorted electric fields, e.g. bumps, protrusions, recesses, slits in pixel electrodes }
G02F 1/133711	{ by organic films, e.g. polymeric films }
G02F 2001/133715	by first depositing a monomer
G02F 1/133719	{ with coupling agent molecules, e.g. silane }
G02F 1/133723	{ Polyimide, polyamide-imide }
G02F 2001/133726	made of a mesogenic material
G02F 2001/13373	Disclination line; Reverse tilt
G02F 1/133734	{ by obliquely evaporated films, e.g. Si or SiO ₂ films }
G02F 2001/133738	for homogeneous alignment
G02F 2001/133742	for homeotropic alignment
G02F 2001/133746	for high pretilt angle, i.e. > 15 degrees
G02F 2001/133749	for low pretilt angle, i.e. < 15 degrees
G02F 1/133753	{ with different alignment orientations or pretilt angles on a same surface, e.g. for grey scale or improved viewing angle }
G02F 2001/133757	with different alignment orientations
G02F 2001/133761	with different pretilt angles
G02F 2001/133765	without a surface treatment
G02F 2001/133769	comprising an active, e.g. switchable alignment layer
G02F 2001/133773	The alignment material or treatment is different for the two opposite substrates
G02F 2001/133776	having structures i.e. unevenness locally influencing the alignment
G02F 1/13378	{ by treatment of the surface, e.g. embossing, rubbing, light irradiation (G02F 1/133711 , G02F 1/133734 , G02F 1/133753 take precedence) }
G02F 1/133784	{ by rubbing }
G02F 1/133788	{ by light irradiation, e.g. linearly polarised light photo-polymerisation }
G02F 2001/133792	by etching
G02F 2001/133796	having conducting property
G02F 1/1339	Gaskets; Spacers, { also spacers with conducting properties (electric line connectors H01R) }; Sealing of the cell
G02F 1/13392	{ spacers dispersed on the cell substrate, e.g. spherical particles, micro-fibres }
G02F 1/13394	{ spacers regularly patterned on the cell substrate, e.g. walls, pillars (G02F 1/133377 takes precedence) }
G02F 2001/13396	Spacers having different sizes
G02F 2001/13398	Materials and properties of the spacer
G02F 1/1341	Filling or closing of the cell { (G02F 1/133365 , G02F 1/1334 take precedence) }
G02F 2001/13415	Drop filling process

G02F 1/1343	Electrodes {(reflective electrodes G02F 1/133553)}
G02F 1/134309	{ characterised by their geometrical arrangement (G09F 9/302 takes precedence) }
G02F 2001/134318	having a patterned common electrode
G02F 1/134327	{ Segmented, e.g. alpha numeric display }
G02F 1/134336	{ Matrix }
G02F 2001/134345	Subdivided pixels, e.g. grey scale, redundancy
G02F 2001/134354	the sub-pixels being capacitively coupled
G02F 1/134363	{ for applying an electric field parallel to the substrate, i.e. in-plane switching (IPS) }
G02F 2001/134372	for fringe field switching [FFS] where the common electrode is not patterned, e.g. planar
G02F 2001/134381	Hybrid switching mode, i.e. for applying an electric field both parallel and orthogonal to the substrates
G02F 1/13439	{ characterised by their electrical, optical, physical properties; materials therefor; method of making }
G02F 1/1345	Conductors connecting electrodes to cell terminals
G02F 1/13452	{ Conductors connecting driver circuitry and terminals of panels (H01L 21/00 takes precedence; electrical details inside the cell G02F 1/133 ;) }
G02F 1/13454	{ Drivers integrated on the active matrix substrate (G02F 1/136277 takes precedence) }
G02F 2001/13456	cell terminals on one side of the display only
G02F 1/13458	{ Terminal pads }
G02F 1/1347	Arrangement of liquid crystal layers or cells in which the final condition of one light beam is achieved by the addition of the effects of two or more layers or cells {(colour projection displays with liquid crystal valves H04N 9/3197)}
G02F 1/13471	{ in which all the liquid crystal cells or layers remain transparent, e.g. FLC, ECB, DAP, HAN, TN, STN, SBE-LC cells (G02F 1/13475 takes precedence) }
G02F 1/13473	{ for wavelength filtering or for colour display without the use of colour mosaic filters }
G02F 1/13475	{ in which at least one liquid crystal cell or layer is doped with a pleochroic dye, e.g. GH-LC cell (G02F 1/13476 takes precedence) }
G02F 1/13476	{ in which at least one liquid crystal cell or layer assumes a scattering state }
G02F 2001/13478	based on selective reflection
G02F 1/135	Liquid crystal cells structurally associated with a photoconducting or a ferro-electric layer, the properties of which can be optically or electrically varied {(G02F 1/133348 takes precedence) }
G02F 2001/1351	light-absorbing or blocking layer
G02F 2001/1352	light-reflecting layer
G02F 1/1354	{ having a particular photoconducting structure or material }
G02F 2001/1355	material or manufacturing process thereof
G02F 2001/1357	electrode structure
G02F 1/1358	{ the supplementary layer being a ferro-electric layer }
G02F 1/136	Liquid crystal cells structurally associated with a semi-conducting layer or

		substrate, e.g. cells forming part of an integrated circuit (G02F 1/135 takes precedence)
G02F 2001/13606	having means for reducing parasitic capacitance
G02F 2001/13613	the semiconductor element is formed on a first substrate and thereafter transferred to the final cell substrate
G02F 1/1362	Active matrix addressed cells {(G02F 1/134336 , G02F 1/134363 take precedence)}
G02F 1/136204	{ Arrangements to prevent high voltage or static electricity failures }
G02F 1/136209	{ Light shielding layers, e.g. black matrix, incorporated in the active matrix substrate, e.g. structurally associated with the switching element }
G02F 1/136213	{ Storage capacitors associated with the pixel electrode }
G02F 2001/136218	Shield electrode
G02F 2001/136222	Color filter incorporated in the active matrix substrate
G02F 1/136227	{ Through-hole connection of the pixel electrode to the active element through an insulation layer }
G02F 2001/136231	for reducing the number of lithographic steps
G02F 2001/136236	using a gray or half tone lithographic process
G02F 1/13624	{ having more than one switching element per pixel }
G02F 2001/136245	having complementary transistors
G02F 2001/13625	Patterning using a multi-mask exposure
G02F 2001/136254	Checking; Testing
G02F 1/136259	{ Repairing; Defects }
G02F 2001/136263	Line defect
G02F 2001/136268	Switch defect
G02F 2001/136272	Auxiliary line
G02F 1/136277	{ formed on a semiconductor substrate, e.g. silicon }
G02F 2001/136281	having a transmissive semiconductor substrate
G02F 1/136286	{ Wiring, e.g. gate line, drain line }
G02F 2001/13629	Multi-layer wirings
G02F 2001/136295	Materials; Compositions; Methods of manufacturing
G02F 1/1365	in which the switching element is a two-electrode device {(G02F 1/136277 takes precedence)}
G02F 1/1368	in which the switching element is a three-electrode device {(G02F 1/136277 takes precedence)}
G02F 2001/13685	Top gate
G02F 1/137	...	characterised by a particular electro- or magneto-optical effect, e.g. field-induced phase transition, orientation effect, guest-host interaction, dynamic scattering
G02F 2001/13706	the LC having positive dielectric anisotropy
G02F 2001/13712	the LC having negative dielectric anisotropy
G02F 1/13718	{ based on a change of the texture state of a cholesteric liquid crystal }
G02F 1/13725	{ based on guest-host interaction (G02F 1/13762 , G02F 1/13737 , take precedence)}
G02F 1/13731	{ based on a field-induced phase transition (G02F 1/13781 takes precedence)}

G02F 1/13737	{ in liquid crystals doped with a plechroic dye }
G02F 1/13743	{ based on electrohydrodynamic instabilities or domain formation in liquid crystals }
G02F 1/1375	{ using dynamic scattering }
G02F 2001/13756	the liquid crystal selectively assuming a light-scattering state (G02F 1/1334 , G02F 1/13718 take precedence)
G02F 1/13762	{ containing luminescent or electroluminescent additives (luminescent materials in general C09K 11/00 ; compositions of liquid crystals comprising additives C09K 19/52 to C09K 19/603 ; electroluminescent light sources H05B 33/00) }
G02F 1/13768	{ based on magneto-optical effects }
G02F 2001/13775	Polymer stabilized liquid crystal layers
G02F 1/13781	{ using smectic liquid crystals (G02F 1/141 takes precedence) }
G02F 2001/13787	Hybrid alignment cells (G02F 1/1393 takes precedence)
G02F 2001/13793	Blue phases
G02F 1/139	based on orientation effects in which the liquid crystal remains transparent
G02F 1/1391	{ Bistable or multi-stable liquid crystal cells (G02F 1/141 takes precedence) }
G02F 1/1392	{ using a field-induced sign-reversal of the dielectric anisotropy }
G02F 1/1393	{ the birefringence of the liquid crystal being electrically controlled, e.g. ECB-, DAP-, HAN-, PI-LC cells (G02F 1/1396 , G02F 1/141 take precedence) }
G02F 1/1395	{ Optically compensated birefringence (OCB)- cells or PI- cells }
G02F 1/1396	{ the liquid crystal being selectively controlled between a twisted state and a non-twisted state, e.g. TN-LC cell (G02F 1/141 takes precedence) }
G02F 1/1397	{ the twist being substantially higher than 90°, e.g. STN-, SBE-, OMI-LC cells }
G02F 2001/1398	the twist being below 90°C
G02F 1/141	using ferroelectric liquid crystals
G02F 2001/1412	Antiferroelectric liquid crystals
G02F 2001/1414	Deformed helix ferroelectric (DHL)
G02F 1/1416	{ Details of the smectic layer structure, e.g. bookshelf, chevron, C1 and C2 }
G02F 1/1418	{ using smectic liquid crystals, e.g. based on the electroclinic effect }
G02F 1/15	..	based on electrochromic elements {(electrochromic materials C09K 9/00)}
G02F 2001/1502	...	complementary cell
G02F 2001/1504	having an inorganic electrochromic layer and a second solid organic electrochromic layer
G02F 1/1506	...	{ based on electrolytic deposition of a non-organic material on or in the vicinity of an electrode }
G02F 1/1508	{ using a solid electrolyte }
G02F 2001/151	...	the electrochromic material comprises ferrocene compounds
G02F 2001/1512	...	the electrochromic layer comprises a mixture of anodic and cathodic compounds
G02F 2001/1515	...	the electrochromic material is made of polymer
G02F 2001/1517	...	based on cyano complex compound, e.g. Prussian blue

G02F 2001/1519	...	the electrolyte is made of polymer
G02F 1/1521	...	{ based on oxidation reduction in organic liquid solutions, e.g. viologens solutions }
G02F 1/1523	...	{ based on solid inorganic materials, e.g. transition metal compounds, e.g. in combination with a liquid or solid electrolyte (G02F 1/1506 takes precedence) }
G02F 1/1525	{ characterised by a particular ion transporting layer, e.g. electrolyte (H01M 6/18 , H01M 10/08 take precedence) }
G02F 1/1527	{ based on iridium oxide or hydroxide }
G02F 1/153	...	Constructional arrangements
G02F 1/1533	{ structural features not otherwise provided for }
G02F 2001/1536	additional, e.g. protective, layer inside the cell
G02F 1/155	Electrodes
G02F 2001/1552	Inner electrode, e.g. the electrochromic layer being sandwiched between the inner electrode and the support substrate---- this group, now to be changed, should already been created by implementation of a previous DOC14 (prior to the one referred to above)----
G02F 2001/1555	Counter electrode
G02F 2001/1557	Side by side arrangements of working and counter electrodes
G02F 1/157	Structural association of optical devices, e.g. reflectors or illuminating devices, with the cell
G02F 1/161	Gaskets; Spacers; Sealing of the cell; Filling or closing of the cell
G02F 1/163	...	Operation of electrochromic cells; Circuit arrangements
G02F 2001/1635	the pixel comprises active switching elements, e.g. TFT
G02F 1/167	..	based on electrophoresis
G02F 2001/1672	...	of the microcup type
G02F 2001/1674	...	comprising a dry toner particle
G02F 2001/1676	...	having a particular electrode
G02F 2001/1678	...	having a particular composition or particle type
G02F 1/17	..	based on variable absorption elements (G02F 1/015 to G02F 1/167 take precedence; { tenebrescent compositions C09K 9/00 })
G02F 1/172	...	{ based on a suspension of orientable dipolar particles, e.g. suspended particles displays }
G02F 1/174	...	{ based on absorption band-shift, e.g. Stark - or Franz-Keldysh effect (G02F 1/015 , G02F 1/178 take precedence) }
G02F 1/176	...	{ using acid- based indicators }
G02F 1/178	...	{ based on pressure effects (G02F 1/195 takes precedence) }
G02F 1/19	..	based on variable reflection or refraction elements ({ G02F 1/01M3 } , G02F 1/015 to G02F 1/167 take precedence)
G02F 1/195	...	{ by using frustrated reflection (digital reflection using controlled total internal reflection G02F 1/315) }
G02F 1/21	..	by interference
G02F 2001/211	...	Sagnac type
G02F 2001/212	...	Mach-Zender type
G02F 2001/213	...	Fabry-Perot type
G02F 2001/215	...	Michelson type

- G02F 1/216 . . . { using liquid crystals, e.g. liquid crystal Fabry-Perot filters }
- G02F 2001/217 . . . Multi mode interference type
- G02F 1/218 . . . { using semi-conducting materials }
- G02F 1/225 . . . in an optical waveguide structure
- G02F 1/2252 { in optical fibres }
- G02F 1/2255 { controlled by a high-frequency electromagnetic component in an electric waveguide structure }
- G02F 1/2257 { the optical waveguides being made of semiconducting material }
- G02F 1/23 . . for the control of the colour ([G02F 1/03](#) to [G02F 1/21](#) take precedence)
- G02F 1/25 . . . as to hue or predominant wavelength

- G02F 1/29 . for the control of the position or the direction of light beams, i.e deflection ({ optical coupling means [G02B 6/26](#) ; optical-mechanical scanning in general [G02B 26/10](#) } ; static stores with electric or magnetic read-in and optical read-out [G11C](#); lasers provided with means to change the location from which, or the direction in which, laser radiation is emitted [H01S 3/101](#))

- G02F 2001/291 . . Two-dimensional analog deflection
- G02F 1/292 . . { by controlled diffraction or phased-array beam steering (controlled diffraction for optical switching [G02F 1/31](#)) }
- G02F 1/293 . . { by another light beam, i.e. opto-optical deflection }
- G02F 2001/294 . . Variable focal length device
- G02F 1/295 . . { Analog deflection from or } in an optical waveguide structure
- G02F 1/2955 . . . { by controlled diffraction or phased-array beam steering (controlled diffraction for optical waveguide switching [G02F 1/313](#)) }
- G02F 1/31 . . Digital deflection, { i.e. optical switching } ([G02F 1/33](#) takes precedence)
- G02F 2001/311 . . . Cascade arrangement of plural switches
- G02F 1/313 . . . in an optical waveguide structure
- G02F 1/3131 { in optical fibres }
- G02F 1/3132 { of directional coupler type (all-optical modulation, gating or switching using a non-linear directional coupler [G02F 1/3521](#)) }
- G02F 1/3133 { the optical waveguides being made of semiconducting materials }
- G02F 1/3134 { controlled by a high-frequency electromagnetic wave component in an electric waveguide structure }
- G02F 2001/3135 vertical structure
- G02F 1/3136 { of interferometric switch type }
- G02F 1/3137 { with intersecting or branching waveguides, e.g. X-switches and Y-junctions }
- G02F 1/3138 { the optical waveguides being made of semiconducting materials }
- G02F 1/315 . . . based on the use of controlled internal reflection
- G02F 1/33 . . Acousto-optical deflection devices ({ circuit or control arrangements therefor [G02F 1/113](#) })
- G02F 1/332 . . . { comprising a plurality of transducers on the same crystal surface, e.g. multi-channel Bragg cell }
- G02F 1/335 . . . having an optical waveguide structure

- G02F 1/35 . Non-linear optics (optical bistable devices [G02F 3/02](#) ; lasers using stimulated Brillouin or Raman effect [H01S 3/30](#))

- G02F 1/3501 .. { Constructional arrangements of non-linear optical devices, e.g. shape of non-linear crystals (constructional arrangements of electro-optic devices [G02F 1/0305](#)) }
- G02F 2001/3503 ... Structural association of optical elements, e.g. lenses, with the nonlinear optical device
- G02F 2001/3505 ... Coatings; Housings; Supports
- G02F 2001/3507 ... Arrangements comprising two or more nonlinear optical devices
- G02F 2001/3509 ... Shape, e.g. shape of end face
- G02F 1/3511 .. { Self-focusing or self-trapping of light; Light-induced birefringence; Induced optical Kerr-effect (photorefractive effects of electro-optic crystals [G02F 1/0338](#) , [G02F 1/0541](#) , of ceramics [G02F 1/0558](#) ; opto-optical modulation [G02F 1/0126](#) ; opto-optical deflection [G02F 1/293](#)) }
- G02F 1/3513 ... { Soliton propagation }
- G02F 1/3515 .. { All-optical modulation, gating, switching, e.g. control of a light beam by another light beam ([G02F 1/353](#) , [G02F 1/37](#) , [G02F 1/39](#) take precedence) }
- G02F 1/3517 ... { using an interferometer }
- G02F 1/3519 { of Sagnac type, i.e. nonlinear optical loop mirror (NOLM) }
- G02F 1/3521 ... { using a directional coupler }
- G02F 1/3523 .. { Non-linear absorption changing by light e.g. bleaching (laser Q-switching using bleachable media [H01S 3/113](#)) }
- G02F 1/3525 .. { Optical damage }
- G02F 1/3526 .. { using two-photon emission or absorption processes (Raman effect [H01S 3/30](#)) }
- G02F 2001/3528 .. for producing a supercontinuum
- G02F 1/353 .. { Frequency conversion, i.e. wherein a light beam with frequency components different from those of the incident light beams is generated (second harmonic generation [G02F 1/37](#) ; optical parametric generation or amplification [G02F 1/39](#) ; transferring the modulation of modulated light [G02F 2/004](#) ; optical pumping of a laser by another laser [H01S 3/094](#) ; nonlinear optical devices inside a laser cavity [H01S 3/108](#)) }
- G02F 1/3532 ... { Arrangements of plural nonlinear devices for generating multi-colour light beams, e.g. arrangements of SHG, SFG, OPO devices for generating RGB light beams }
- G02F 1/3534 ... { Three-wave interaction, e.g. sum-difference frequency generation ([G02F 1/3532](#) takes precedence) }
- G02F 1/3536 ... { Four-wave interaction }
- G02F 1/3538 { for optical phase conjugation ([H01S 3/10076](#) takes precedence) }
- G02F 2001/354 ... Third or higher harmonic generation
- G02F 2001/3542 ... Multi-pass arrangements, i.e. arrangements to pass light a plurality of times through the same element, e.g. by using an enhancement cavity
- G02F 1/3544 ... { Particular phase matching techniques }
- G02F 2001/3546 Active phase matching, e.g. by electro- or thermo-optic tuning
- G02F 2001/3548 Quasi-phase-matching (QPM), e.g. using a periodic domain inverted structure
- G02F 1/355 .. characterised by the materials used
- G02F 1/3551 ... { Crystals }
- G02F 1/3553 { having the formula $MTiOYO_4$, where M=K, Rb, Tl, NH₄ or Cs and Y=P or As, e.g. KTP }
- G02F 1/3555 ... { Glasses }

- G02F 1/3556 . . . { Semiconductor materials, e.g. quantum wells }
- G02F 1/3558 . . . { Poled materials, e.g. with periodic poling; Fabrication of domain inverted structures, e.g. for quasi-phase-matching (QPM) }
- G02F 1/361 . . . Organic materials
- G02F 1/3611 { containing Nitrogen }
- G02F 1/3612 { Heterocycles having N as heteroatom }
- G02F 1/3613 { containing Sulfur }
- G02F 1/3614 { Heterocycles having S as heteroatom }
- G02F 1/3615 { containing polymers }
- G02F 1/3616 { having the non-linear optical group in the main chain }
- G02F 1/3617 { having the non-linear optical group in a side chain }
- G02F 1/3618 { Langmuir Blodgett Films }
- G02F 1/3619 { Organometallic compounds }
- G02F 1/365 . . in an optical waveguide structure ([G02F 1/377](#) , { [G02F 1/395](#) }take precedence)
- G02F 1/37 . . for second-harmonic generation {([G02F 1/3532](#) takes precedence) }
- G02F 2001/372 . . . means for homogenizing the output beam
- G02F 2001/374 . . . Cerenkov radiation
- G02F 1/377 . . . in an optical waveguide structure
- G02F 1/3775 { with a periodic structure, e.g. domain inversion, for quasi-phase-matching (QPM) ([G02F 1/383](#) takes precedence) }
- G02F 1/383 of the optical fibre type
- G02F 1/39 . . for parametric generation or amplification of light, infra-red or ultra-violet waves ({ [G02F 1/3532](#) takes precedence; } electrical parametric amplifiers [H03F 7/00](#))
- G02F 2001/392 . . . Parametric amplification
- G02F 1/395 . . . { in optical waveguides }
- G02F 1/397 . . . { Amplification of light by wave mixing involving an interference pattern, e.g. using photorefractive material }

- G02F 2/00** **Demodulating light; Transferring the modulation of modulated light; Frequency-changing of light** ([G02F 1/35](#) takes precedence; photoelectric detecting or measuring devices [G01J](#), [H01J 40/00](#) , [H01L 31/00](#) ; demodulating laser arrangements { e.g. switching, gating } [H01S 3/10](#) ; demodulation or transference of modulation of modulated electro-magnetic waves in general [H03D 9/00](#))

- G02F 2/002 . { using optical mixing (homodyne, heterodyne systems [H04B 10/148](#)) }
- G02F 2/004 . { Transferring the modulation of modulated light, i.e. transferring the information from one optical carrier of a first wavelength to a second optical carrier of a second wavelength, e.g. all-optical wavelength converter }
- G02F 2002/006 . . All-optical wavelength conversion
- G02F 2002/008 . . Opto-electronic wavelength conversion, i.e. involving photo-detection of the first optical carrier

- G02F 2/02 . Frequency-changing of light, e.g. by quantum counters (luminescent materials [C09K 11/00](#))

- G02F 3/00** **Optical logic elements** ({ optical computing [G06E](#) } ; electric pulse generators using

opto-electronic devices as active elements [H03K 3/42](#) ; logic circuits using opto-electronic devices [H03K 19/14](#)); **Optical bistable devices**

- G02F 3/02 . Optical bistable devices
- G02F 3/022 .. { based on electro-, magneto- or acousto-optical elements ([G02F 3/028](#) takes precedence) }
- G02F 3/024 .. { based on non-linear elements, e.g. non-linear Fabry-Perot cavity ([G02F 3/028](#) takes precedence) }
- G02F 3/026 .. { based on laser effects }
- G02F 3/028 .. { based on self electro-optic effect devices (SEED) }

G02F 7/00 Optical analogue/digital converters

NOTE

This group covers only converters based in substantial manner on elements which are provided for in group [G02F 1/00](#) .

G02F 2201/00 Constructional arrangements not provided for in groups [G02F 1/00](#) to [G02F 7/00](#)

- G02F 2201/02 . fibre
- G02F 2201/04 . monomode
- G02F 2201/05 . multimode
- G02F 2201/06 . integrated waveguide
- G02F 2201/063 .. ridge; rib; strip loaded
- G02F 2201/066 .. channel; buried
- G02F 2201/07 . buffer layer
- G02F 2201/08 . light absorbing layer
- G02F 2201/083 .. infra-red absorbing
- G02F 2201/086 .. UV absorbing
- G02F 2201/12 . electrode
- G02F 2201/121 .. common or background
- G02F 2201/122 .. having a particular pattern
- G02F 2201/123 .. pixel
- G02F 2201/124 .. interdigital
- G02F 2201/125 .. delta-beta
- G02F 2201/126 .. push-pull
- G02F 2201/127 .. travelling wave
- G02F 2201/128 .. field shaping

- G02F 2201/14 . asymmetric
- G02F 2201/15 . periodic
- G02F 2201/16 . series; tandem
- G02F 2201/17 . Multi-pass arrangements, i.e. arrangements to pass light a plurality of times through the same element, e.g. by using an enhancement cavity
- G02F 2201/18 . parallel
- G02F 2201/20 . delay line
- G02F 2201/205 . . of fibre type
- G02F 2201/30 . grating
- G02F 2201/302 . . grating coupler
- G02F 2201/305 . . diffraction grating
- G02F 2201/307 . . Reflective grating, i.e. Bragg grating
- G02F 2201/34 . reflector
- G02F 2201/343 . . cholesteric liquid crystal reflector
- G02F 2201/346 . . distributed (Bragg) reflector
- G02F 2201/36 . Airflow channels, e.g. constructional arrangements facilitating the flow of air
- G02F 2201/38 . Anti-reflection arrangements
- G02F 2201/40 . Arrangements for improving the aperture ratio
- G02F 2201/42 . Arrangements for providing conduction through an insulating substrate
- G02F 2201/44 . Arrangements combining different electro-active layers, e.g. electrochromic, liquid crystal or electroluminescent layers
- G02F 2201/46 . Fixing elements
- G02F 2201/465 . . Snap -fit
- G02F 2201/48 . Flattening arrangements
- G02F 2201/50 . Protective arrangements
- G02F 2201/501 . . Blocking layers, e.g. against migration of ions
- G02F 2201/503 . . Arrangements improving the resistance to shock
- G02F 2201/505 . . Arrangements improving the resistance to acoustic resonance like noise
- G02F 2201/506 . . Repairing, e.g. with redundant arrangement against defective part
- G02F 2201/508 . . . Pseudo repairing, e.g. a defective part is brought into a condition in which it does not disturb the functioning of the device
- G02F 2201/52 . RGB geometrical arrangements

- G02F 2201/54 . Arrangements for reducing warping-twist
- G02F 2201/56 . Substrates having a particular shape, e.g. non-rectangular
- G02F 2201/58 . Arrangements comprising a monitoring photodetector

G02F 2202/00 Materials and properties

- G02F 2202/01 . dipole
- G02F 2202/02 . organic material
- G02F 2202/021 . . low molecular weight
- G02F 2202/022 . . polymeric
- G02F 2202/023 . . . curable
- G02F 2202/025 thermocurable
- G02F 2202/026 . . charge transfer complex
- G02F 2202/027 . . Langmuir-Blodgett film
- G02F 2202/028 . . photobleached
- G02F 2202/04 . dye
- G02F 2202/043 . . pleochroic
- G02F 2202/046 . . fluorescent
- G02F 2202/06 . dopant
- G02F 2202/07 . poled
- G02F 2202/08 . glass transition temperature
- G02F 2202/09 . inorganic glass
- G02F 2202/10 . semiconductor
- G02F 2202/101 . . G_xAs and alloy
- G02F 2202/102 . . In_xP and alloy
- G02F 2202/103 . . a-Si
- G02F 2202/104 . . poly-Si
- G02F 2202/105 . . single crystal Si
- G02F 2202/106 . . Cd_xSe or Cd_xTe and alloys
- G02F 2202/107 . . Zn_xS or Zn_xSe and alloys
- G02F 2202/108 . . quantum wells
- G02F 2202/12 . photoconductor
- G02F 2202/13 . photorefractive
- G02F 2202/14 . photochromic

- G02F 2202/16 . conductive
- G02F 2202/20 . LiNbO₃, LiTaO₃
- G02F 2202/22 . Antistatic materials or arrangements
- G02F 2202/28 . Adhesive materials or arrangements
- G02F 2202/30 . Metamaterials
- G02F 2202/32 . Photonic crystals
- G02F 2202/34 . Metal hydrides materials
- G02F 2202/36 . Micro or nano materials
- G02F 2202/38 . Sol-gel materials
- G02F 2202/40 . Materials having a particular birefringence, retardation
- G02F 2202/42 . Materials having a particular dielectric constant
- G02F 2202/99 . Test HW
- G02F 2203/00 Function characteristic**
- G02F 2203/01 . transmissive
- G02F 2203/02 . reflective
- G02F 2203/023 . . total internal reflection
- G02F 2203/026 . . attenuated or frustated internal reflection
- G02F 2203/03 . scattering
- G02F 2203/04 . wavelength independent
- G02F 2203/05 . wavelength dependent
- G02F 2203/055 . . wavelength filtering
- G02F 2203/06 . Polarisation independent
- G02F 2203/07 . Polarisation dependent
- G02F 2203/09 . transfective
- G02F 2203/10 . plasmon
- G02F 2203/11 . involving infrared radiation
- G02F 2203/12 . spatial light modulator

- G02F 2203/13 . involving THZ radiation
- G02F 2203/15 . involving resonance effects, e.g. resonantly enhanced interaction
- G02F 2203/16 . involving spin polarization effects
- G02F 2203/17 . involving soliton waves
- G02F 2203/18 . adaptive optics, e.g. wavefront correction
- G02F 2203/19 . linearised modulation; reduction of harmonic distortions
- G02F 2203/20 . Intrinsic phase difference, i.e. optical bias, of an optical modulator; Methods for the pre-set thereof
- G02F 2203/21 . Thermal instability, i.e. DC drift, of an optical modulator; Arrangements or methods for the reduction thereof
- G02F 2203/22 . diffractive
- G02F 2203/24 . beam steering
- G02F 2203/25 . Frequency chirping of an optical modulator; Arrangements or methods for the pre-set or tuning thereof
- G02F 2203/255 . . Negative chirp
- G02F 2203/26 . Pulse shaping; Apparatus or methods therefor
- G02F 2203/28 . focussing or defocussing
- G02F 2203/30 . Gray scale
- G02F 2203/34 . Colour display without the use of colour mosaic filters
- G02F 2203/48 . Variable attenuator
- G02F 2203/50 . Phase-only modulation
- G02F 2203/52 . Optical limiters
- G02F 2203/54 . Optical pulse train (comb) synthesizer
- G02F 2203/56 . Frequency comb synthesizer
- G02F 2203/58 . Multi-wavelength, e.g. operation of the device at a plurality of wavelengths
- G02F 2203/585 . . Add/drop devices
- G02F 2203/60 . Temperature independent
- G02F 2203/62 . Switchable arrangements whereby the element being usually not switchable
- G02F 2203/64 . Normally black display, i.e. the off state being black

- G02F 2203/66 . Normally white display, i.e. the off state being white
- G02F 2203/68 . Green display, e.g. recycling, reduction of harmful substances
- G02F 2203/69 . Arrangements or methods for testing or calibrating a device
- G02F 2203/70 . Semiconductor optical amplifier [SOA] used in a device covered by [G02F](#)
- G02F 2413/00** **Indexing scheme related to [G02F 1/13363P](#) , i.e. to birefringent elements, e.g. for optical compensation, characterised by the number, position, orientation or value of the compensation plates**
- G02F 2413/01 . Number of plates being 1
- G02F 2413/02 . Number of plates being 2
- G02F 2413/03 . Number of plates being 3
- G02F 2413/04 . Number of plates greater than or equal to 4
- G02F 2413/05 . Single plate on one side of the LC cell
- G02F 2413/06 . Two plates on one side of the LC cell
- G02F 2413/07 . All plates on one side of the LC cell
- G02F 2413/08 . with a particular optical axis orientation
- G02F 2413/09 . with a spatial distribution of the retardation value
- G02F 2413/10 . with refractive index ellipsoid inclined, or tilted, relative to the LC-layer surface O plate
- G02F 2413/105 . . with varying inclination in thickness direction, e.g. hybrid oriented discotic LC
- G02F 2413/11 . The refractive index N_z perpendicular to the element surface being different from in-plane refractive indices N_x and N_y , e.g. C plate
- G02F 2413/12 . Biaxial compensators
- G02F 2413/13 . Positive birefringence
- G02F 2413/14 . Negative birefringence
- G02F 2413/15 . with twisted orientation, e.g. comprising helically oriented LC-molecules or a plurality of twisted birefringent sublayers